30	NANOTECHNOLOGY RELATED INTEGRATED	128	PLDs
	CIRCUIT DESIGN	129	Global
50	DESIGN OF SEMICONDUCTOR MASK OR	130	Detailed
	RETICLE	131	With partitioning
51	.Analysis and verification	132	.Optimization
	(process flow, inspection)	133	For power
52	Defect (including design rule	134	For timing
	checking)	135	For area
53	Optical proximity correction	136	.Testing or Evaluating
	(including RET)	137	.PCB, MCM Design
54	.Manufacturing optimizations	138	.System-on-chip design
55	Layout generation (polygon,	139	.Layout editor (with ECO, reuse,
33	pattern feature)		GUI)
56	.Yield		
100	INTEGRATED CIRCUIT DESIGN		
100	PROCESSING		
101	.Logic design processing	FORETCN	ART COLLECTIONS
102	Design entry	FOREIGN	ART COLLECTIONS
102		EOD 100	GERGIETE PROTON (71.6./1)
103	<pre>Translation (logic-to-logic, logic-to-netlist, netlist</pre>		CIRCUIT DESIGN (716/1)
	processing)	FOR IUI	Optimization (e.g., redundancy,
104		EOD 100	compaction) (716/2)
104	Logic circuit synthesis (mapping logic)	FOR 102	.Translation (e.g., conversion,
105	With partitioning	EOD 103	equivalence) (716/3)
105			.Testing or evaluating (716/4)
100	Design verification (functional	FOR 104	Design verification (e.g.,
107	simulation, model checking)		wiring line capacitance,
107	Equivalence checking		fanout checking, minimum path
100	Timing verification (timing	EOD 105	width) (716/5)
100	analysis)	FOR 105	Timing analysis (e.g., delay
109	Power estimation		time, path delay, latch
110	.Physical design processing	EOD 106	timing) (716/6)
111	Verification	FOR 106	.Partitioning (e.g., function
112	Defect Analysis		block, ordering constraint)
113	Timing Analysis	EOD 107	(716/7) .Floorplanning (716/8)
114	Buffer or repeater insertion		
115	Noise (e.g., crosstalk,	FOR 100	Detailed placement (i.e.,
116	electromigration, etc.)	EOD 100	<pre>iterative improvement) (716/9)Constraint-based placement</pre>
116	Mapping circuit design to	FOR 109	(e.g., critical block
	programmable logic devices		assignment, delay limits,
110	(PLDs)		wiring capacitance) (716/10)
117	Configuring PLDs (including	<b>₽∩₽</b> 11∩	
	data file, bitstream	POK 110	Layout editor (e.g., updating) (716/11)
110	generation, etc.)	EOD 111	.Routing (e.g., routing map,
118	Floorplanning	POK III	netlisting) (716/12)
119	Placement or layout	<b>⊡</b> ∩D 112	Global routing (e.g., shortest
120	Power distribution	POR IIZ	path, dead space, or duplicate
121	For PLDs		trace elimination) (716/13)
122	Constraint-based	FO₽ 113	Detailed routing (e.g., channel
123	Iteration	1.01/ 113	routing, switch box routing(
124	With partitioning		(716/14)
125	With partitioning	FOR 11/	PCB wiring (716/15)
126	Routing		PLA, PLD, FPGA, OR MCM (716/16)
127	Power (voltage islands)	LOV II3	LLA, FLD, FEGA, OR MCM (/IO/IO)

## 716 - 2 CLASS 716 716 COMPUTER-AIDED DESIGN AND ANALYSIS OF CIRCUITS AND SEMICONDUCTOR MASKS

- FOR 116 .Programmable integrated circuit (e.g., basic cell, standard cell, macrocell) (716/17)
- FOR 117 .Logical circuit synthesizer (716/18)
- FOR 118 DESIGN OF SEMICONDUCTOR MASK (716/19)
- FOR 119 .Mesh generation (716/20)
- FOR 120 .Pattern exposure (716/21)

APPLICATIONS (364/400)

FOR 000 CLASS-RELATED FOREIGN DOCUMENTS

Any foreign patents or non-patent literature from subclasses that have been reclassified have been transferred directly to FOR Collections listed below. These Collections contain ONLY foreign patents or non-patent literature. The parenthetical references in the Collection titles refer to the abolished subclasses from which these Collections were derived.

FOR 489 .Circuit design and analysis (364/489)

FOR 490 ..Integrated (364/490) FOR 491 ...Layout (364/491)